

ABSTRACT OF THE DISCLOSURE

In one embodiment, a system for delivering radio frequency (RF) power to a plasma processing system includes an automatic impedance matching network configured to receive RF power from an RF generator, and a fixed impedance matching
5 network coupled between the automatic impedance matching network and the plasma processing chamber. The fixed impedance matching network may be configured to transform a first impedance presented by the chamber to a second impedance that allows the automatic impedance matching network to operate within a tuning range.